Search Notes				

Application/Control No.	Applicant(s)/Patent under Reexamination	
10/676,976	GLEW ET AL.	
Examiner	Art Unit	·
Stephen W. Smoot	2813	

SEARCHED					
Subclass	Date	Examiner			
31	12/17/2004	sws			
481	12/17/2004	sws			
494	12/17/2004	sws			
507	12/17/2004	sws			
695	12/17/2004	sws			
58	12/17/2004	sws			
95	12/17/2004	sws			
104	12/17/2004	sws ノ			
	Subclass  31  481  494  507  695  58  95	Subclass         Date           31         12/17/2004           481         12/17/2004           494         12/17/2004           507         12/17/2004           695         12/17/2004           58         12/17/2004           95         12/17/2004			

ass	Date	Examiner
1		

SEARCH NOTES (INCLUDING SEARCH STRATEGY)			
	DATE	EXMR	
Key Words: SAGE - Selective Area Growth and Etch;	12/17/2004	I.W.L. sws	
Mask - Wafer, Substrate; Epitaxy; CVD.	12/17/2004	J.V.J sws	
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	12/17/2004	LV.S.	
PLUS Search	12/15/2004	S.W.J.	